

Resource Summary Report

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Oxford: Atomfab ALD Plasma Technology

RRID:SCR_020350

Type: Tool

Proper Citation

Oxford: Atomfab ALD Plasma Technology (RRID:SCR_020350)

Resource Information

URL: <https://plasma.oxinst.com/products/atomic-layer-deposition/atomfab>

Proper Citation: Oxford: Atomfab ALD Plasma Technology (RRID:SCR_020350)

Description: Uses remote source specifically designed for atomic scale processing. Has low damage for sensitive substrates, fast cycle times and reliability with uniform plasma exposure and film deposition, short plasma times, 250ms, short strike time, 80ms, for high throughput, and reproducible strike time and low reflected power for high yield.

Resource Type: instrument resource

Keywords: Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEDit,

Availability: Commercially available

Resource Name: Oxford: Atomfab ALD Plasma Technology

Resource ID: SCR_020350

Alternate IDs: Model_Number_Atomfab

Record Creation Time: 20220129T080349+0000

Record Last Update: 20260829T182652+0000

Ratings and Alerts

No rating or validation information has been found for Oxford: Atomfab ALD Plasma Technology.

No alerts have been found for Oxford: Atomfab ALD Plasma Technology.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.